

Fig. 2

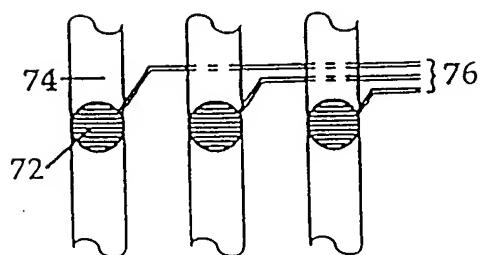


Fig. 3A

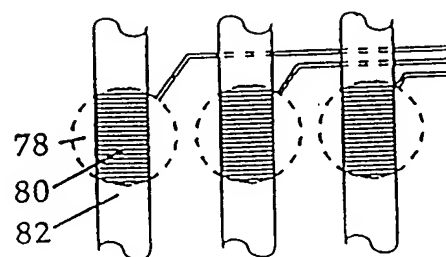


Fig. 3B

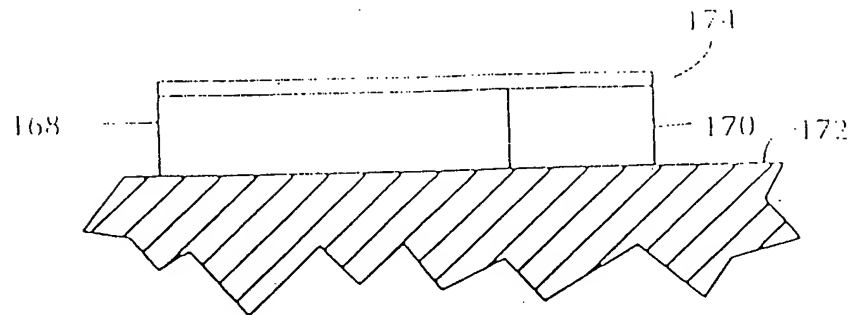


Fig. 4A

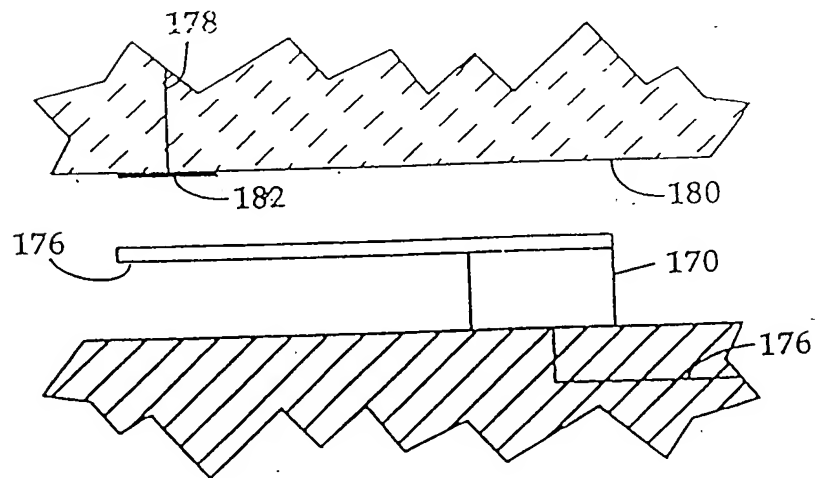


Fig. 4B

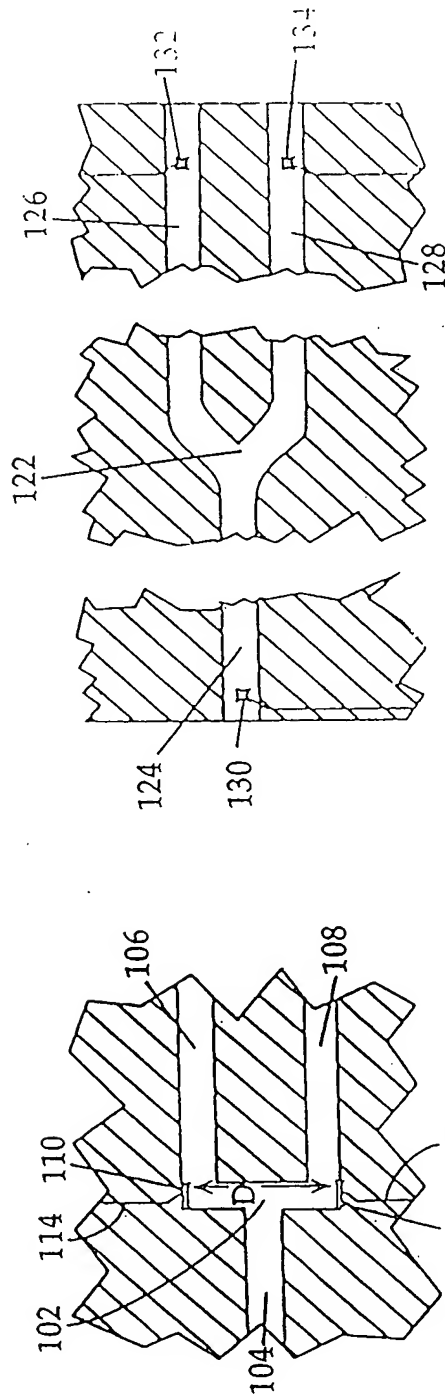


Fig. 5B

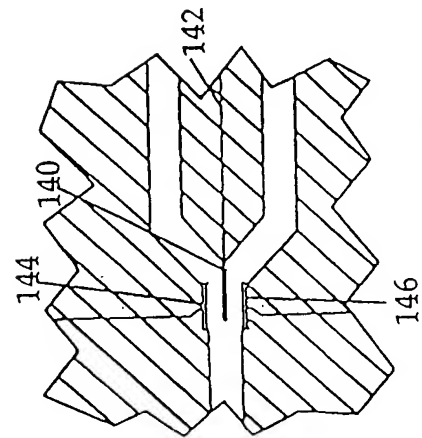


Fig. 5C

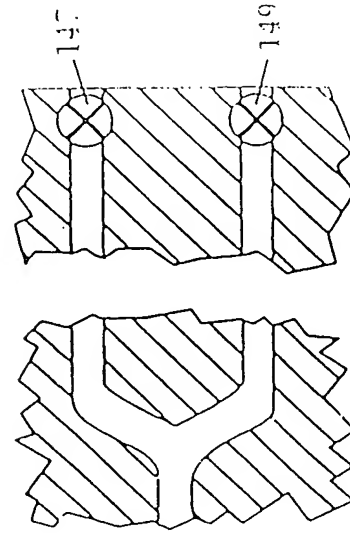


Fig. 5D

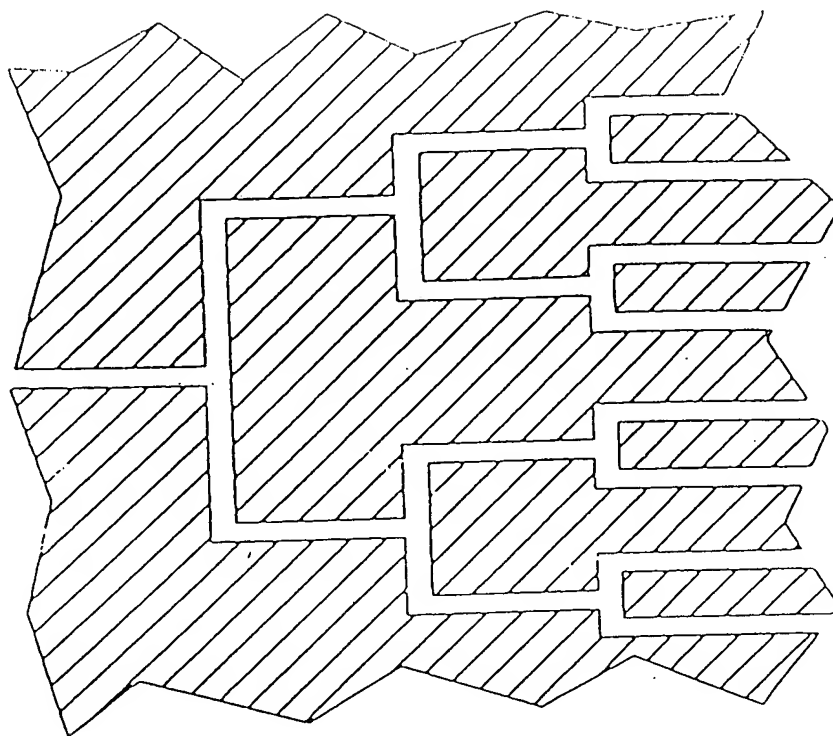


Fig. 6

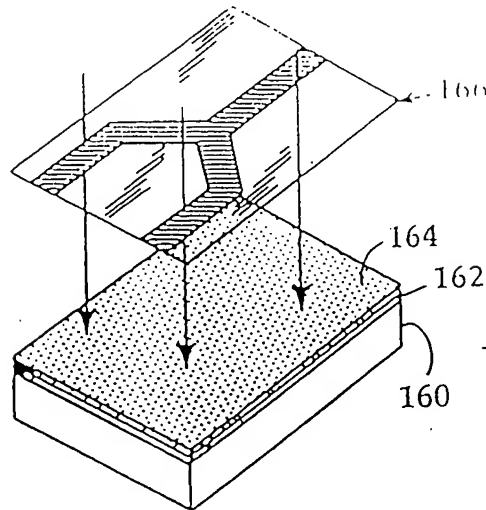


Fig. 7A

develop
and rinse

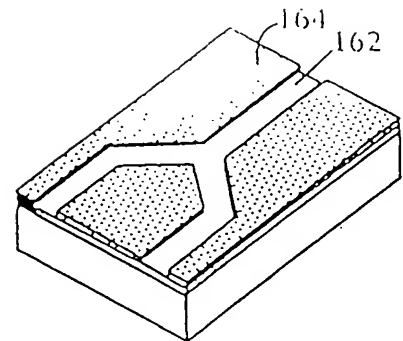


Fig. 7B

1. etch SiO_2
2. remove resist

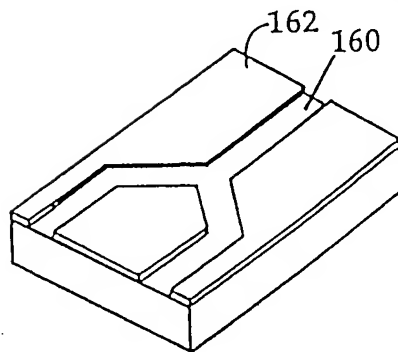


Fig. 7C

etch Si

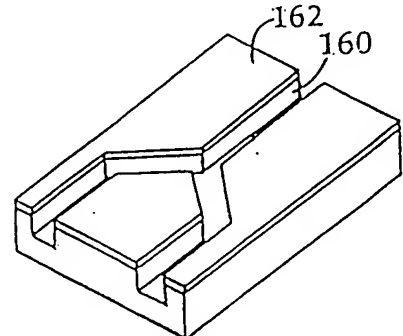


Fig. 7D

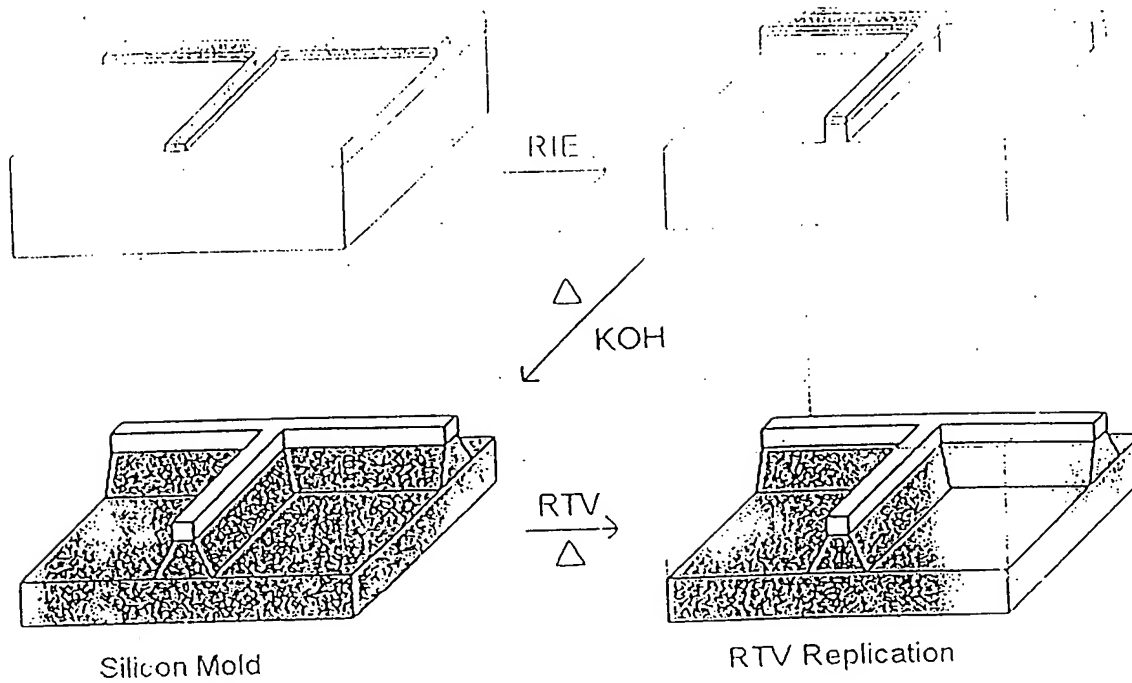
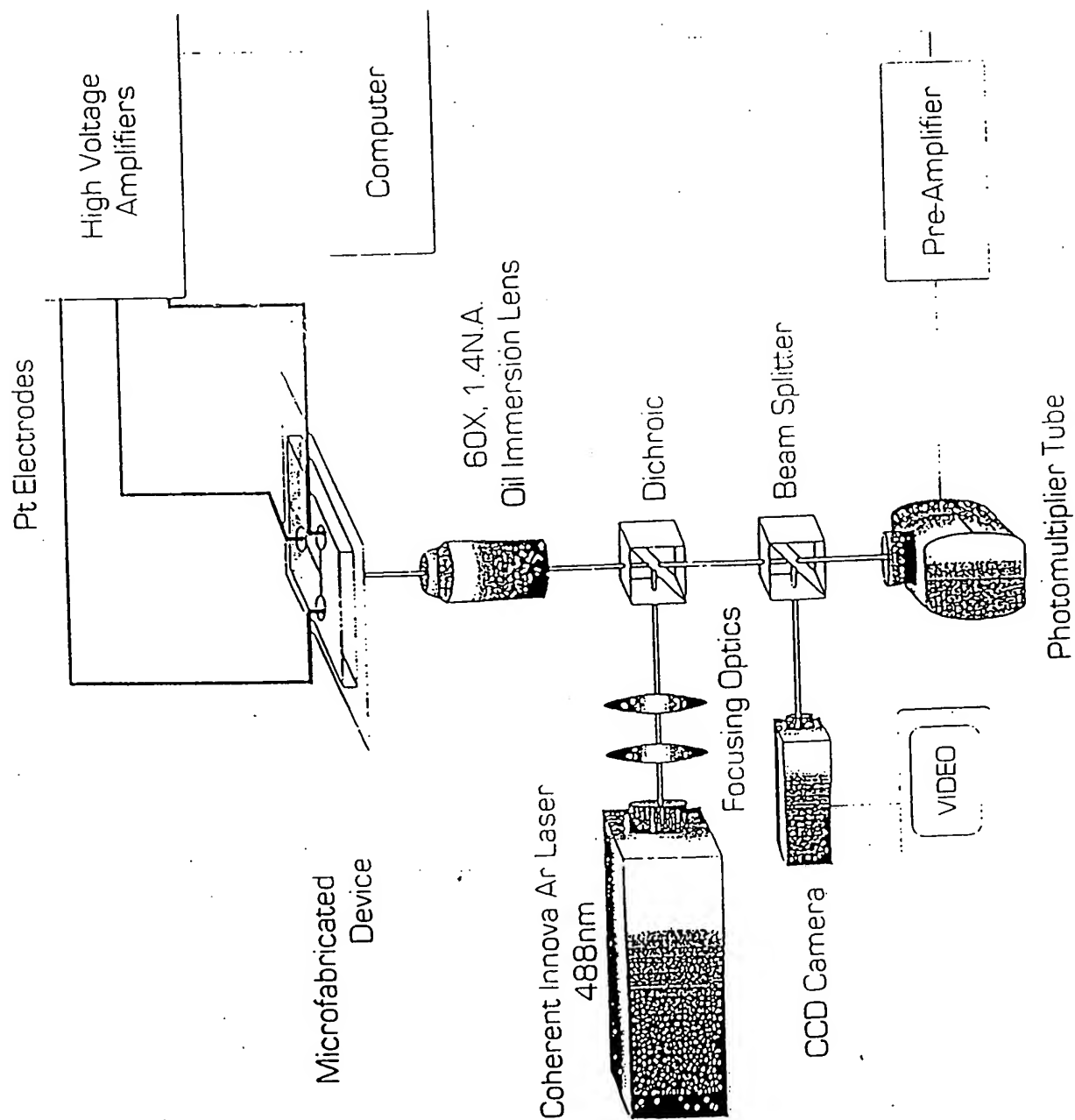


Fig. 8



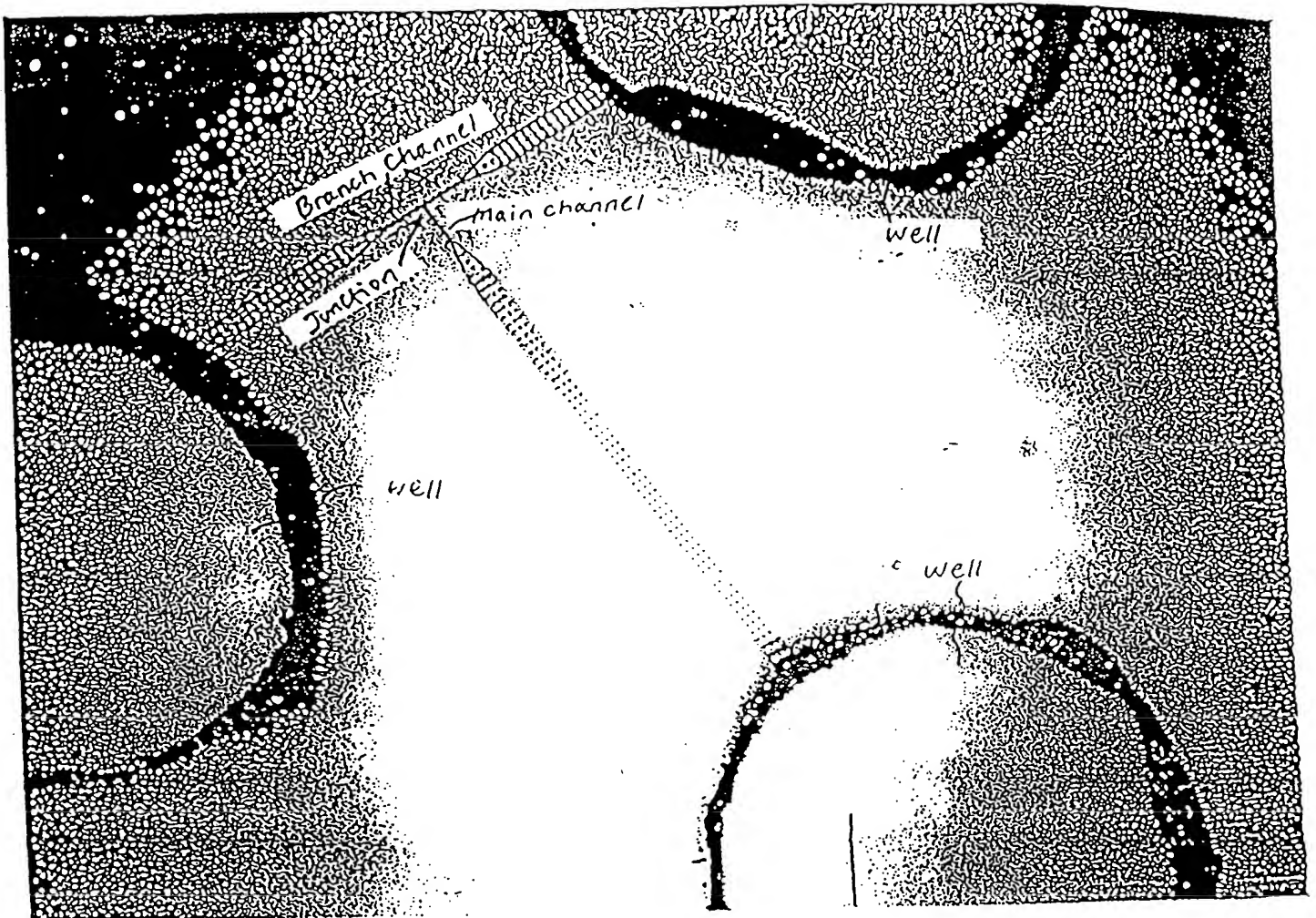


Fig 10

Fig. 11

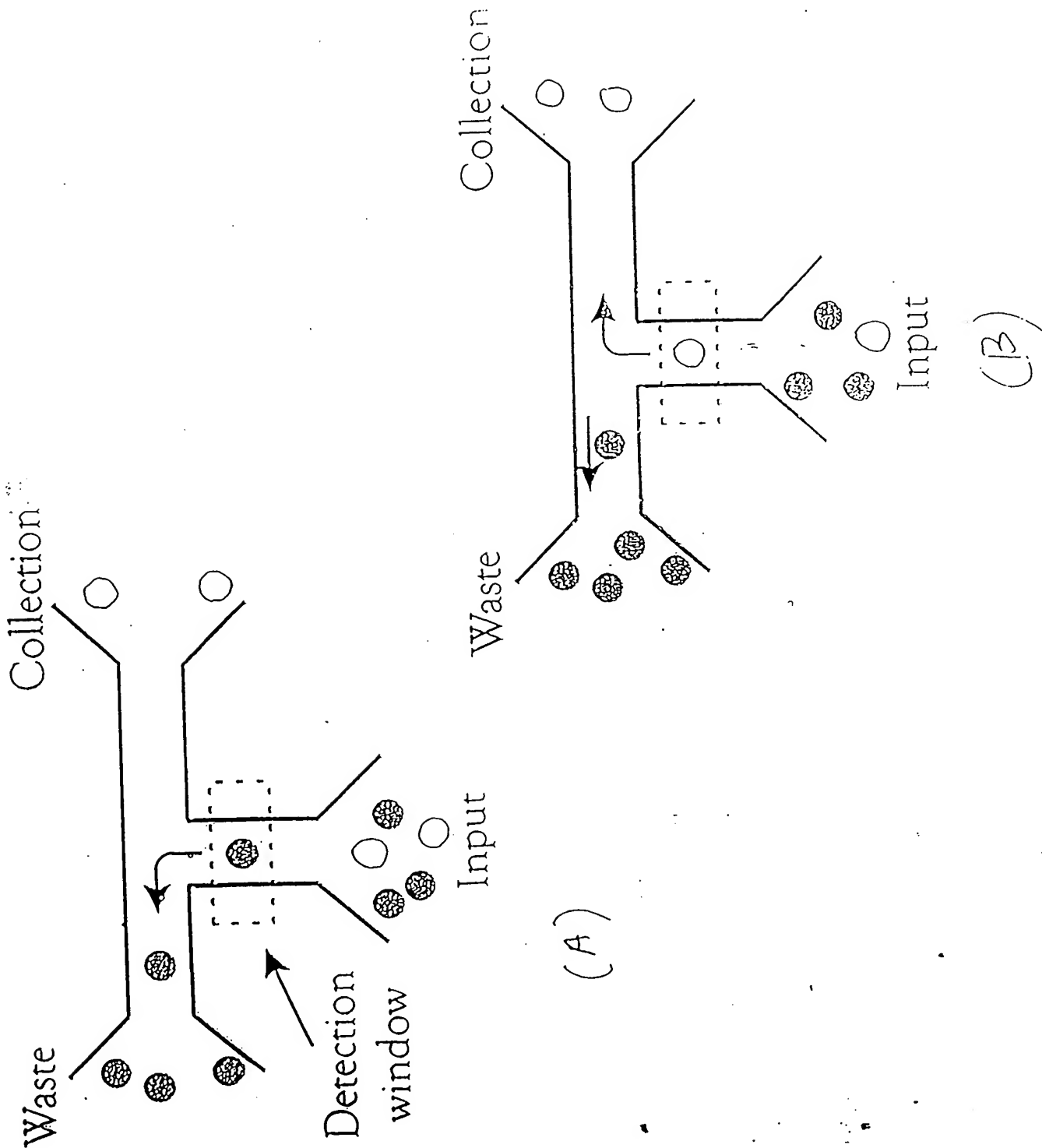
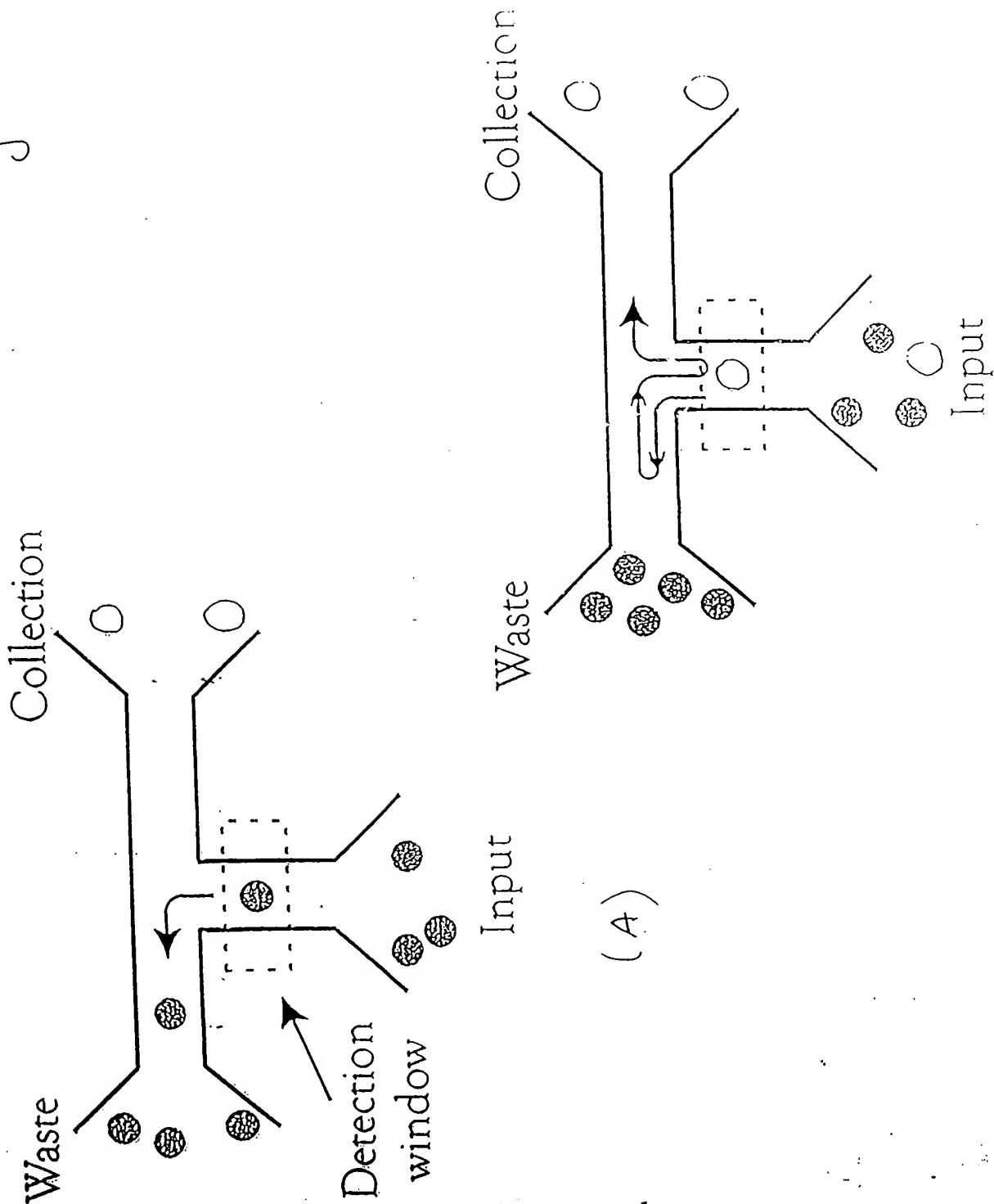


Fig 12



(B)

(A)

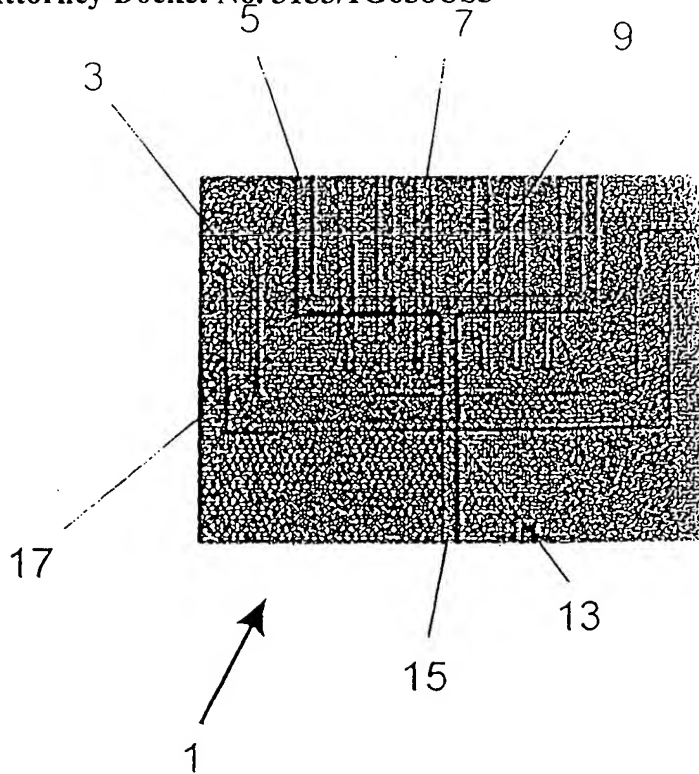


FIG. 13A

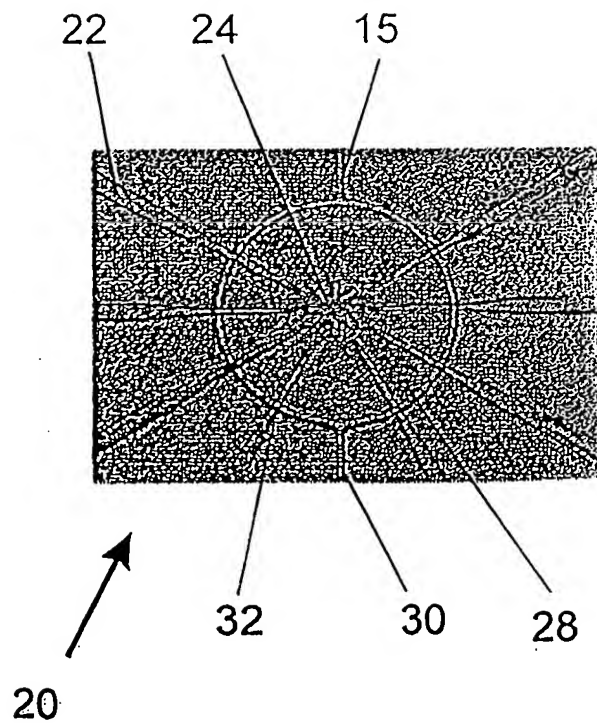


FIG. 13B

FIG. 14

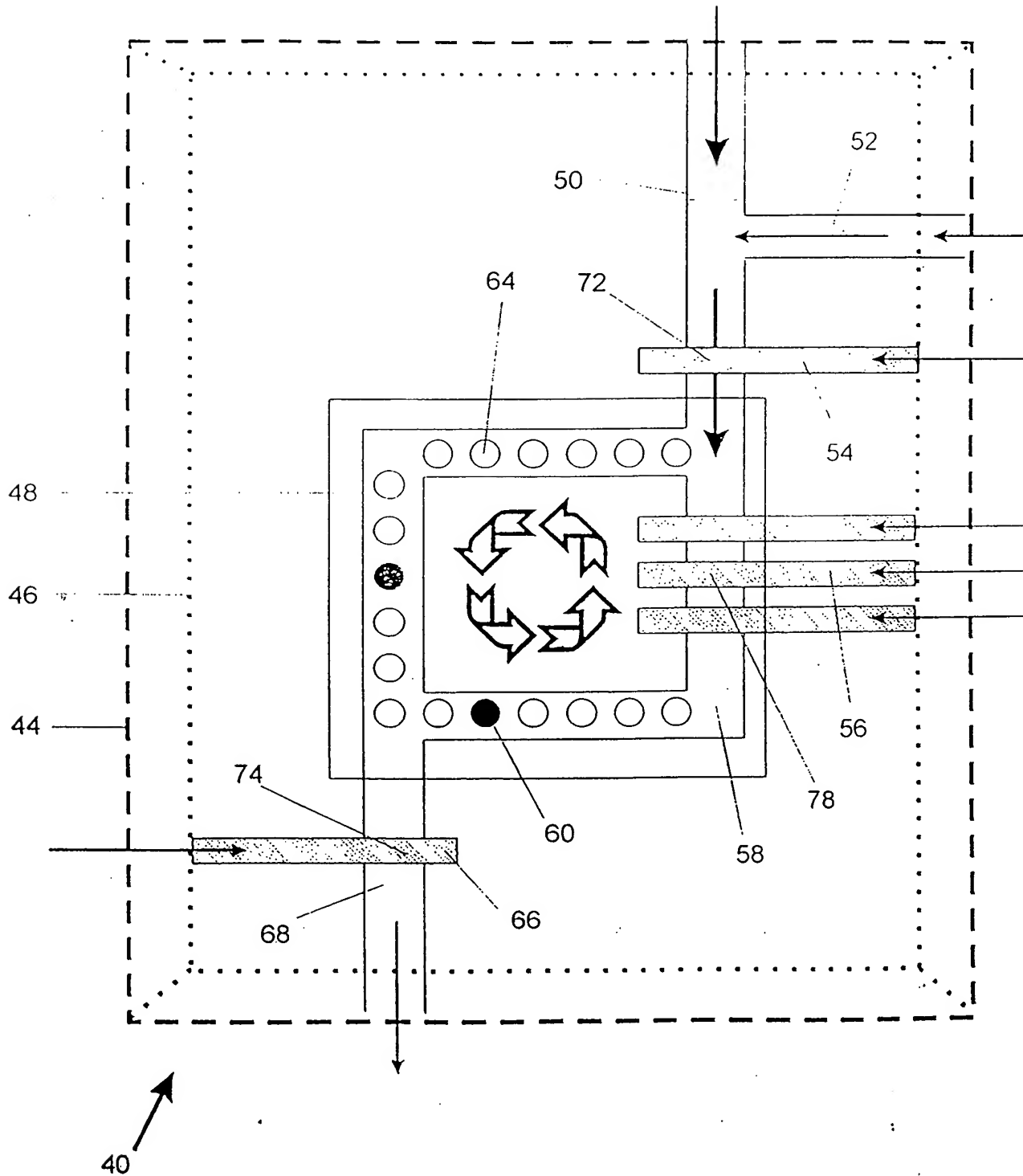


FIG. 15

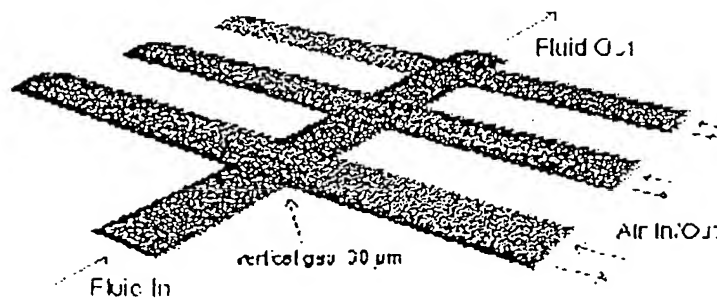


FIG. 16A

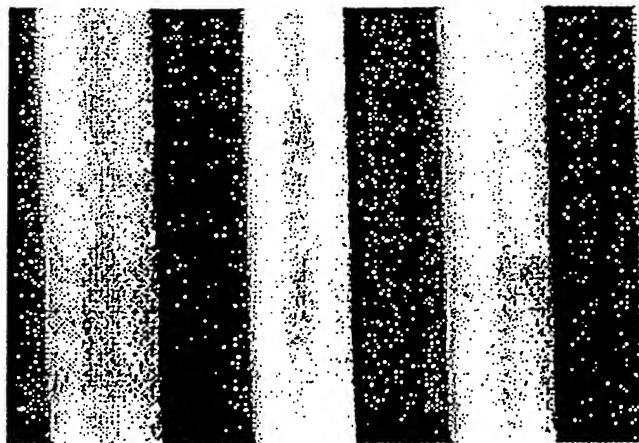


FIG. 16B

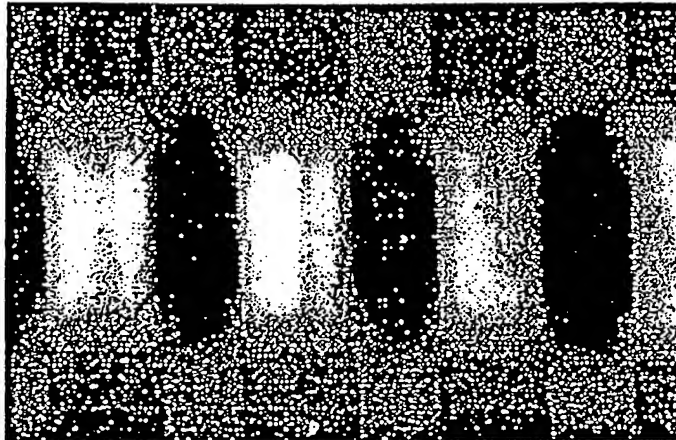


FIG. 16C

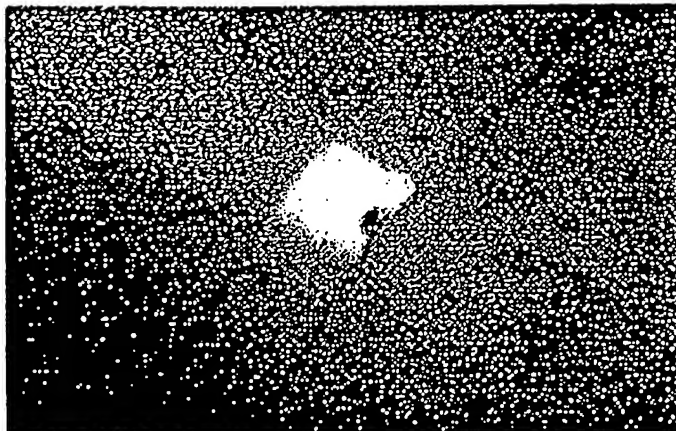
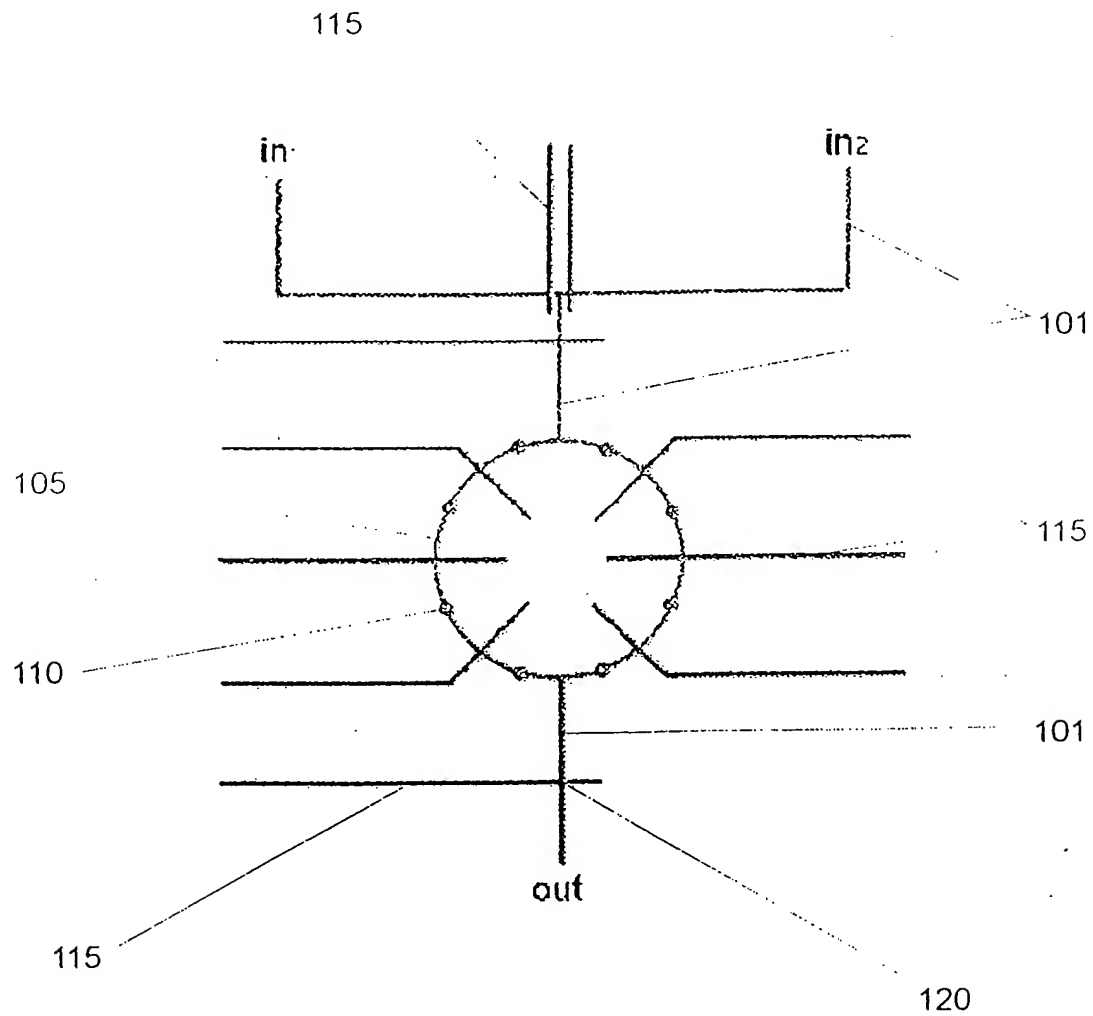
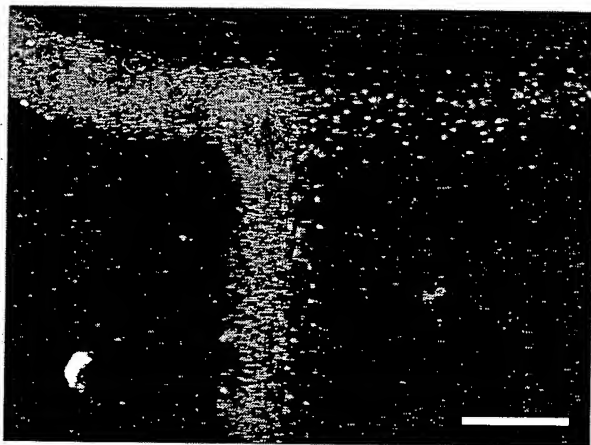


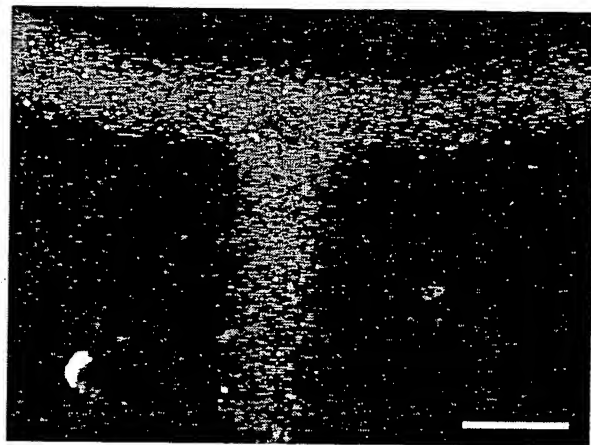
FIG. 17





(a).

FIG. 18A



(b).

FIG. 18B

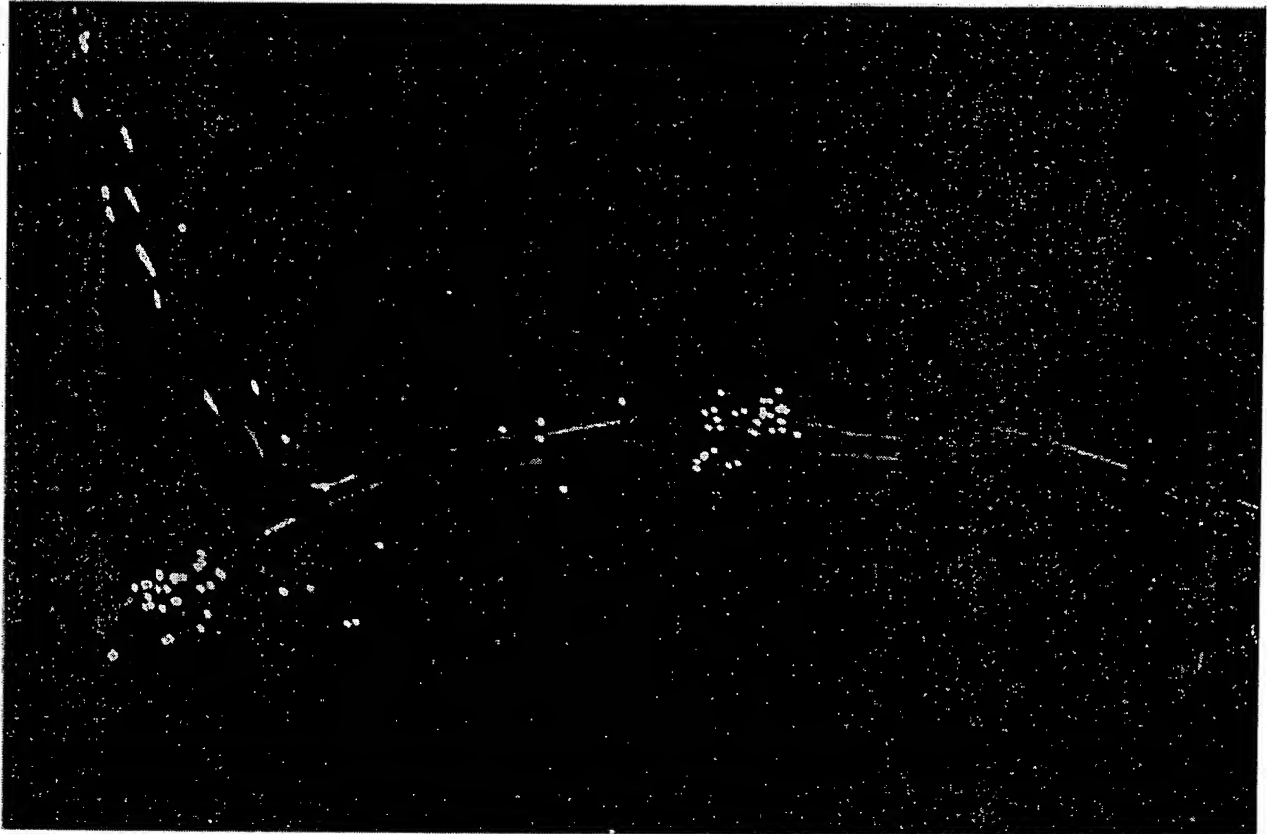


FIG. 19

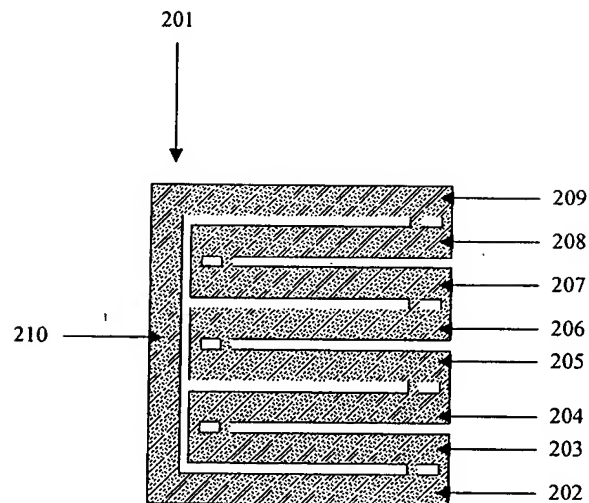


FIG. 20

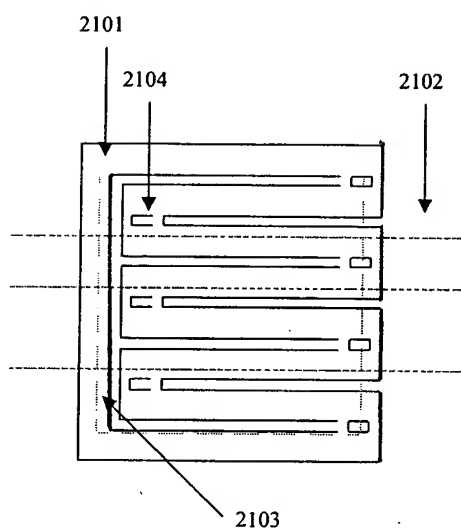


FIG. 21A

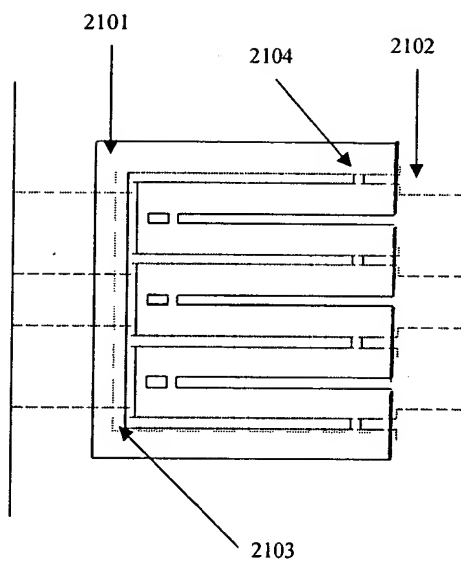
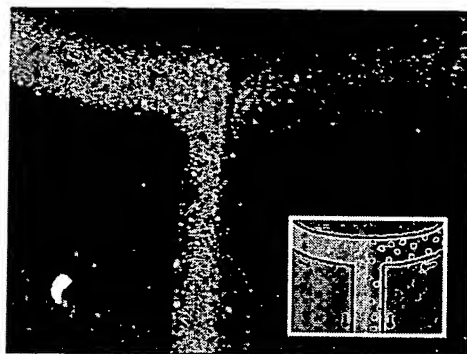
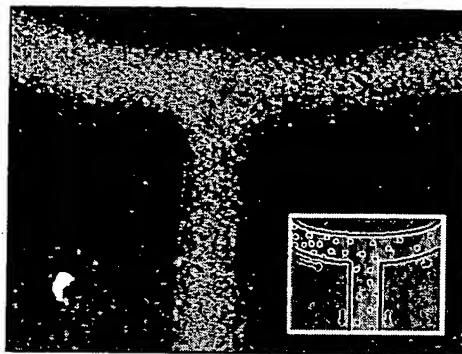


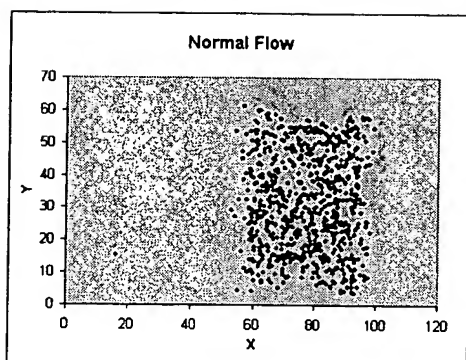
FIG. 21B



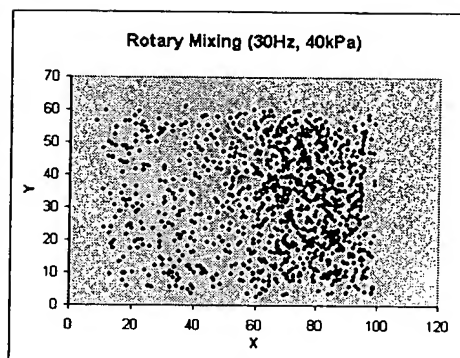
(a).



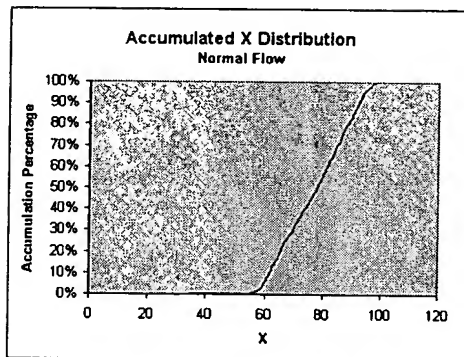
(b).



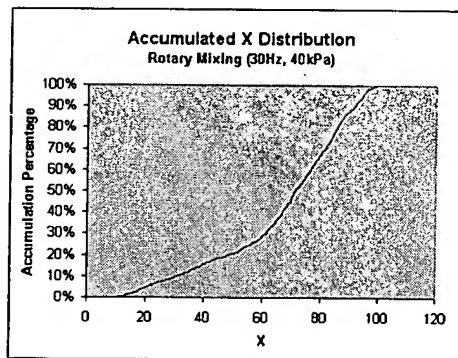
(c).



(d).



(e).



(f).

FIG. 23

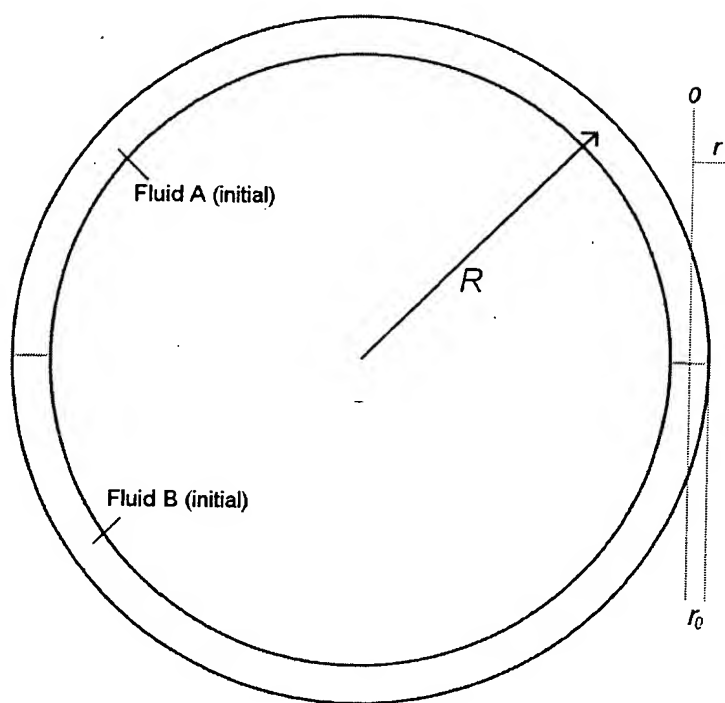


FIG. 24